



High-precision photolithography and glass machining

PRODUCT DATASHEET

Glass Photomask

SUBSTRATE & COATING

Substrate Material	Sodalime, Quartz (fused silica)- Other substrate on request
Standard coating	Low reflective chrome @435 nm
Optionnal coating	High reflective chrome. Low reflective chrome at specific wavelenght

PATTERN & RESOLUTION

Minimum Feature / Line Width	Down to 0.6 μm
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DIMENSIONS

Dimensions	3×3 inches to 28x32 inches
Customized size	Custom size available on request

USE CASES

Quartz substrates support deep-UV exposure and are commonly used in the following applications:

1	Micro-optics
2	Semiconductors
3	MEMS



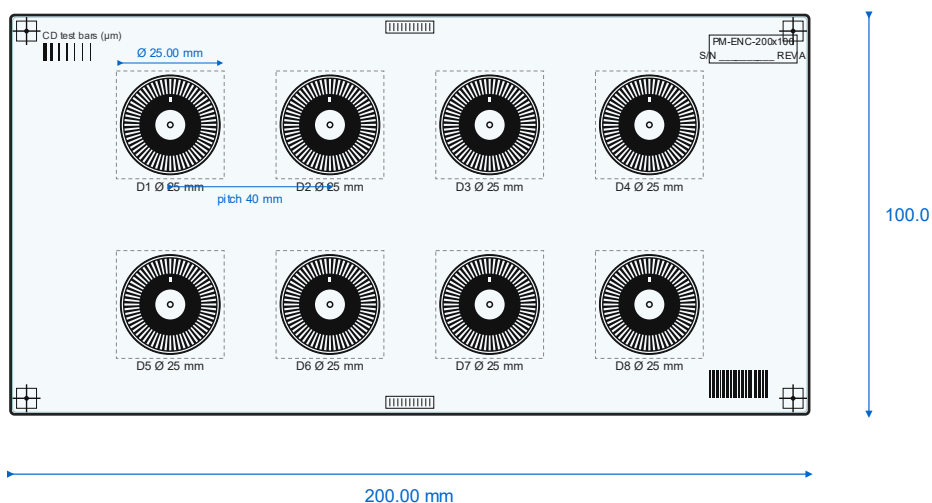
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PHOTOMASK — ENCODER DISK ARRAY / 200 × 100 mm

Quartz glass substrate, chrome pattern — 8 × Ø 25 mm rotary encoder disks

Part No. PM-ENC-200x100 / Polarity: clear-field (chrome features = opaque)



HOW TO ORDER

Glass photomasks are manufactured to order. Please provide the following information when requesting a quotation:

- 1 Mask dimensions
- 2 Minimum features size
- 3 Input data: GDS,CIF,DXF, Gerber 274X
- 4 Substrate material
- 5 Required quantity and delivery timeframe

Request a Quote

Contact us for custom glass photomask solutions tailored to your application and specifications.

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** All values are nominal. Selba reserves the right to update specifications without prior notice. Custom tolerances and special requirements available on request.*